

Elettra Sincrotrone Trieste



UHV experiments

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Coordinators of the Microscopy/Diffraction Beamlines Groups





- The surface science case in research (e.g. catalysis, interfaces, sensors).
- Photoemission spectroscopy and microscopy.
- Instrumentation requirements.
- Examples and technologies for the future





Escamicroscopy - SPEM layout





Spatial resolution



Best ZP: D=200 μ m, dr=50 nm

Other sizes: D=250 μ m, dr=100nm D=250 μ m, dr=80nm



50 nm test object

Spectromicroscopy: real beam size and shape

135 nm (SPEM)









Horizontal scan



Chemical imaging





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Degradation of light emitting diodes (in collaboration with P. Melpignano CRP, R. Zamboni CNR-ISMN)



OLED Display Screen (from Universal Display Corp.)



Dark spot in OLED

Al



increasing voltage and operating time

P. Melpignano et al. Appl. Phys. Lett. 86, 041105 (2005),

"Clean" experiment: OLED growth and operated in the **SPEM (UHV ambient) : failure** due to light emission



S. Gardonio et al. Org. Electr. 8 (1), 37-43, (2007)



Operating SOFC: mass transport

(in collaboration with M. Backhaus- Corning Inc. - USA)



Strongly constraining experimental setup



- Real samples
 High T = 650-700° C
 pO₂=1x10⁻⁶ mbar
 Applied potentials

 -2V<U<+2V

 Surface sensitive technique
- High lateral resolution

Elemental distribution at electrolyte/LSM interface



Surface composition change with bias



Observation and explanation of electrochemical cathode activation

- •Strong current increase under negative bias when Mn spreads on electrolyte
- •Mn2+ electrolyte surface enrichment→electrolyte surface conductivity → direct oxygen incorporation into electrolyte
- •Oxygen incorporation extends under bias from TPB to the entire electrolyte surface

M. Backhaus et al. Solid State Ionics 179 (2008) 891–895, M. Backhaus et al. Advances in Solid Oxide Fuel Cells III 28 (4), 2007.



For many samples/experiments a CLEAN surface is crucial





How fast clean surfaces get dirty

Pressure (Torr)	Time to produce 1 ML (seconds)
760	3.44 x 10 ⁻⁹
1	2.61 x 10 ⁻⁶
1 x 10 ⁻³	2.61 x 10 ⁻³
1 x 10 ⁻⁶	2.61
1 x 10 ⁻⁹	2.61 x 10 ³
1 x 10 ⁻¹¹	2.61 x 10 ⁵



- Annealing
- O (2), H (2), bath
- Sputtering
- Vacuum exposure
- Capping



Materials and equipment



Contactless monitoring of the diameter-dependent conductivity of GaAs nanowires

(in collaboration with S. Rubini – CNR-IOM Laboratory - Italy)







Debye lengths~d

Influence of size (temperature and surface treatment) on the conductance of individual low-doped GaAs NWs can be addressed and quantified by contactless measurements of the photon beam-induced surface potential along a NW axis using photoelectron microspectroscopy



New approaches for UHV environments



Electron analyzers

- The most used type of electron analyzer is the Hemispherical Electron Analyzer (HEA)
- Due to geometrical constrains the detection in mainly grazing





Electron analyzer of the SPEM



Electron detectors based on microchannel plates



The Microchannel Plate (MCP) consists of millions of very-thin, conductive glass capillaries (4 to 25 micro meters in diameter) fused together and sliced into a thin plate. Each capillary or channel works as an independent secondary-electron multiplier to form a two-dimensional secondary-electron multiplier.



Environmental cell with graphene oxide windows (in collaboration with A. Kolmakov – Souther Illinois Uni. - USA)



Graphene/Au: SPEM

Graphene layers are transparent to photoelectrons



A. Kolmakov et al. *Nature Nanotechnology* 6, 651–657 (2011)



A. Kolmakov et al. Nature Nanotechnology 6, 651–657 (2011) and Nanoscale 2014, DOI: 10.1039/C4NR03561E







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